

**METHOD AND APPARATUS FOR ADJUSTING THE THICKNESS OF A
LAYER OF SEMICONDUCTOR MATERIAL**

ABSTRACT

5 A method for adjusting the thickness of a thin
semiconductor material layer. The technique includes
measuring the layer to establish a thickness profile,
comparing the measured thickness profile with stored
standard profiles, wherein each standard profile is
10 stored in association with respective thickness
adjustment specifications, selecting a stored standard
profile to associate the layer with the respective
thickness adjustment specification, and adjusting the
thickness of the layer in accordance with the thickness
15 adjustment specification. The invention also provides
apparatus for adjusting the thickness of a thin
semiconductor material layer.